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McNally et al.(10) **Pub. No.: US 2023/0230821 A1**(43) **Pub. Date: Jul. 20, 2023**(54) **SYSTEM AND METHOD FOR REMOTE  
SENSING A PLASMA****Publication Classification**(51) **Int. Cl.**  
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(IE)(57) **ABSTRACT**(21) Appl. No.: **17/946,189**(22) Filed: **Sep. 16, 2022****Related U.S. Application Data**(63) Continuation of application No. 16/498,049, filed on  
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The invention provides a method and system to remotely monitor a plasma (3) comprising a magnetic field antenna (2) positioned in the near electromagnetic field of a coupled plasma source wherein the magnetic field antenna is a magnetic loop antenna placed in the near electromagnetic field and measure near field signals emitted from the plasma source. A radio system (1) is utilised to analyse the low power signal levels across a wide frequency band. Plasma parameters such as series, or geometric, resonance plasma and electron-neutral collision frequencies are evaluated via a fitting of resonant features present on higher harmonics of the driving frequency to identify arcing, pump or matching failure events, common in fabrication plasma systems.

